

10/069656

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[20103 00201]

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s) : SMIRNOV et al.  
Serial No. : To Be Assigned  
Filed : Herewith  
For : DEVICE FOR FORMING NANOSTRUCTURES ON THE SURFACE OF A SEMICONDUCTOR WAFER BY MEANS OF ION BEAMS  
Art Unit : To Be Assigned  
Examiner : To Be Assigned

Commissioner for Patents  
Washington, D.C. 20231

**PRELIMINARY AMENDMENT AND**  
**37 C.F.R. § 1.125 SUBSTITUTE SPECIFICATION STATEMENT**

SIR:

Please amend the above-identified application before examination, as set forth below.

**IN THE SPECIFICATION AND ABSTRACT:**

In accordance with 37 C.F.R. § 1.121(b)(3), a Substitute Specification (including the Abstract, but without claims) accompanies this response. It is respectfully requested that the Substitute Specification (including Abstract) be entered to replace the Specification of record.

**IN THE CLAIMS:**

Without prejudice, please cancel original claims 1 -- 3, and please add new claims 4 -- 8 as follows:

4. (New) A system for forming nanostructures on a surface of a semiconductor wafer, comprising:
  - a. a vacuum chamber having exhaust and annealing systems;
  - b. an input device inputting a semiconductor wafer into the vacuum chamber;